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INFORMATION DISCLOSURE STATEMENT BY APPLICANT(S)

(Use as many sheets as necessary)

Sheet 1 of 3

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| ı | Application Number | 10/533,822 | | | | |
| | Filing Date | August 31, 2005 | | | | |
| | First Named Inventor | Mino Green | | | | |
| | Art Unit | 2815 | | | | |
| | Examiner Name | Jami M. Valentine | | | | |
| | Attorney Docket No. | KSTR 2 00004 | | | | |

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| Publication Date | Name of Patentee or | | | | | |

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| (Use | as many | sheets as necessary) | Examiner Name | | | Jami M. Valentine | | |
| | Sh | eet 2 of 3 | Attorney Doo | ket No. | · | KSTR 2 00004 | | |
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| | | | Examiner Name | | | Jami M. Valentine | |
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| Examiner | /Jami Valentine/ | Date Considered | 03/21/2008 |
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